

WHAT IS CLAIMED IS:

1. A two-dimensional phase type element having plural segments, wherein an alignment error between segments is limited to a local portion.

2. A method of manufacturing a two-dimensional phase type element, comprising the steps of:

forming, on a substrate, a first etching mask in a checkered pattern; and

performing an etching process while using the mask as a reference.

3. A method of manufacturing a two-dimensional phase type element, comprising the steps of:

forming, on a substrate, a first etching mask in a checkered pattern;

forming segments of multiple levels at a portion not covered by the first mask;

forming a second etching mask corresponding to an inversion of the first etching mask;

removing the first etching mask; and

forming segments of multiple levels at a portion not covered by the second etching mask.

4. A method according to Claim 2 or 3, wherein the first etching mask is formed by a chromium film.

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5. A method according to Claim 2 or 3, wherein the first etching mask consists of aluminum.

5 6. A method according to Claim 2 or 3, wherein the first etching mask consists of aluminum and wherein the second etching mask consists of chromium.

10 7. A method according to Claim 2 or 3, wherein the first etching mask consists of chromium and wherein the second etching mask consists of aluminum.

15 8. A method according to any one of Claims 2 - 7, wherein the substrate contains quartz.

20 9. A method according to any one of Claims 2 - 8, wherein a reticle having an optical proximity effect correcting pattern is used to form the etching mask of checkered pattern through photolithography.

25 10. A method according to any one of Claims 2 - 9, wherein the etching process is carried out by use of the etching mask and an etching mask formed by a resist.

30 11. A method according to any one of Claims 2 - 10, further comprising molding an element while using, as a mold, a substrate on which plural segments of



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